10th WORKSHOP EUV-FEL

January 28, 2026
13:10-16:55 JST Hybrid
Akihabara UDX Gallery NEXT / Conference NEXT1
Akihabara UDX 4F, 4-14-1, Sotokanda, Chiyodaku, Tokyo

EUV-FEL Light Source Study Group for Industrialization, iCASA/ KEK

Keynote lecturer:
Prof. Junji Yumoto (The University of Tokyo)
Dr. Nicholas Kelez (xLight Inc. , CEO & CTO)

Invited speakers:
Prof. Yosuke Honda (KEK)
Prof. Takeo Ejima (Tohoku University)

Session Chairs
Seiji Nagahara
Hakaru Mizoguchi
Hiroshi Kawata

10th WORKSHOP

EUV-FEL

January 28, 2026

13:10-16:55 JST **Hybrid**

Akihabara UDX Gallery NEXT / Conference NEXT1
Akihabara UDX 4F, 4-14-1, Sotokanda, Chiyodaku, Tokyo

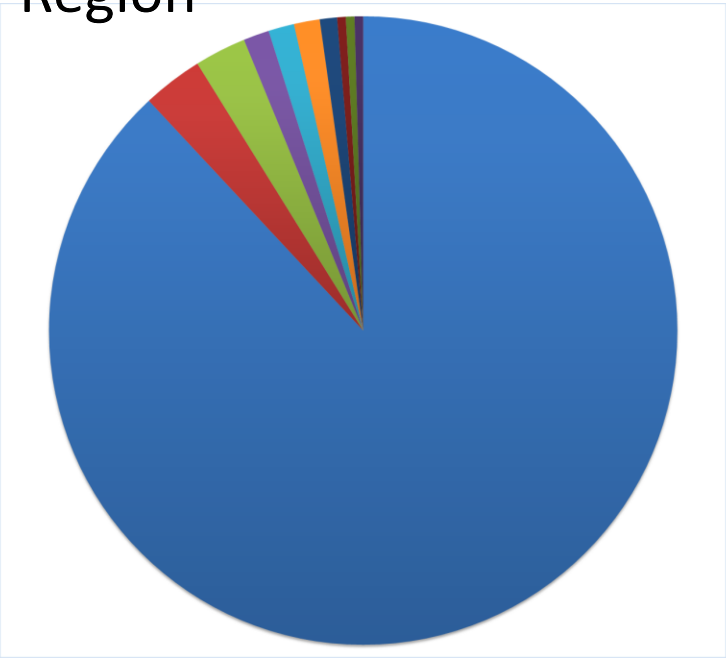
EUV-FEL Light Source Study Group for Industrialization, iCASA/ KEK

Participants

Number of registers; 226 @27/January/2026

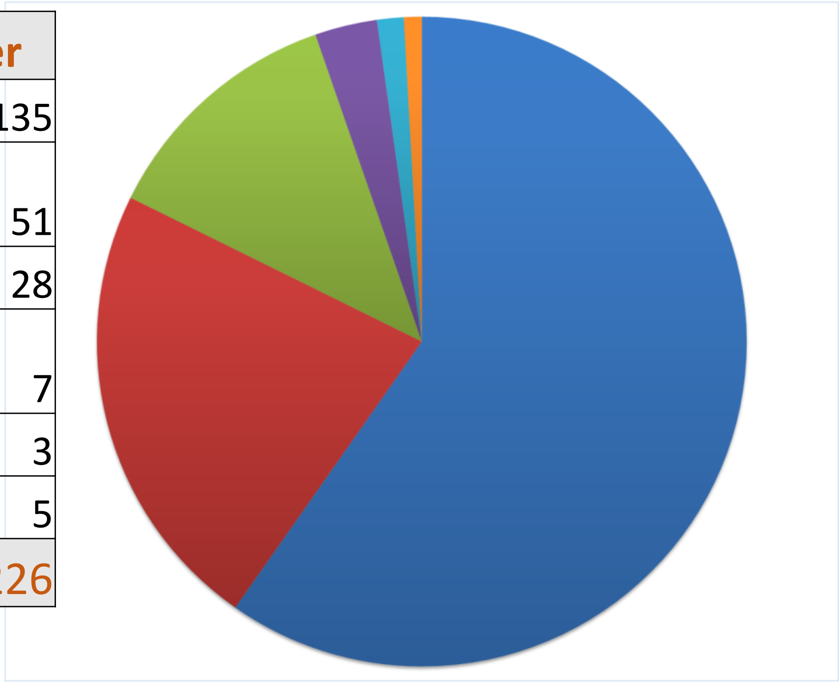
Region	Number
Japan	199
United States	7
China	6
Slovenia	3
South Korea	3
Belgium	3
Taiwan	2
Hong Kong SAR China	1
Germany	1
India	1
Total	226

Region



Affiliation	Number
Company	135
Research institution	51
University	28
Government office	7
Consultant	3
?	5
Total	226

Affiliation



10th WORKSHOP

EUV-FEL

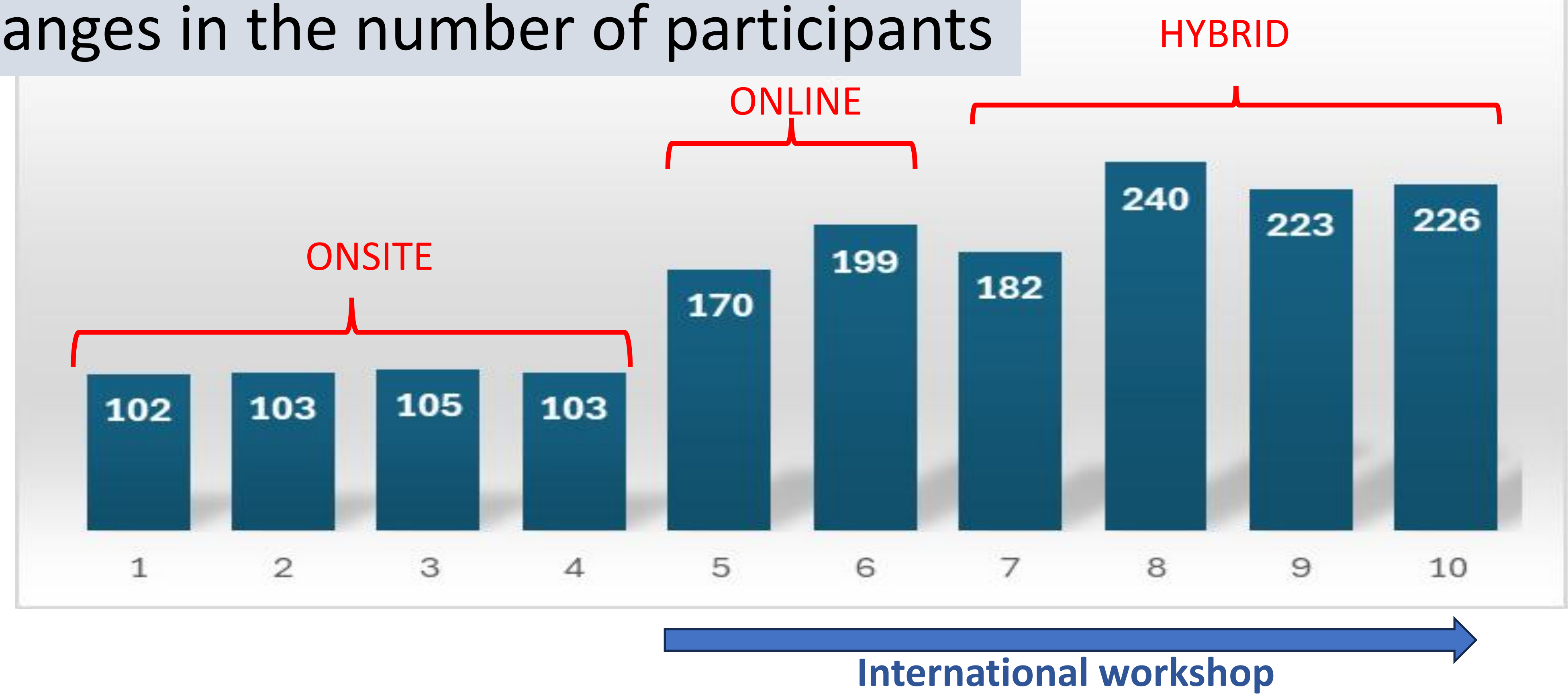
January 28, 2026

13:10-16:55 JST Hybrid

Akihabara UDX Gallery NEXT / Conference NEXT1
Akihabara UDX 4F, 4-14-1, Sotokanda, Chiyodaku, Tokyo

EUV-FEL Light Source Study Group for Industrialization, iCASA/ KEK

Changes in the number of participants



10th WORKSHOP

EUV-FEL

January 28, 2026

13:10-16:55 JST **Hybrid**

Akihabara UDX Gallery NEXT / Conference NEXT1

Akihabara UDX 4F, 4-14-1, Sotokanda, Chiyodaku, Tokyo

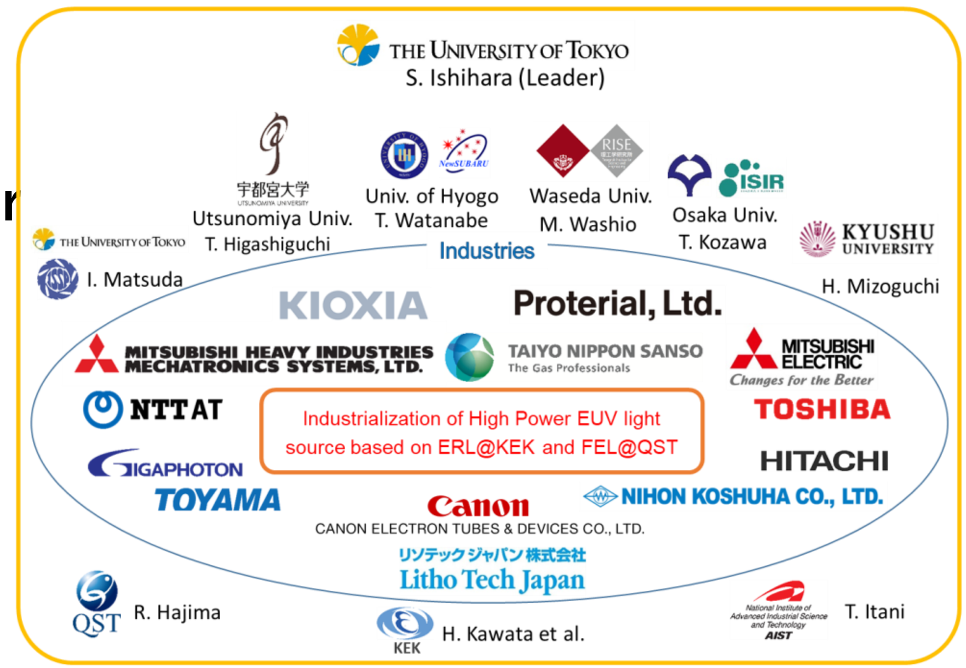
EUV-FEL Light Source Study Group for Industrialization, iCASA/ KEK

Organizers

EUV-FEL Light Source Study Group for Industrialization
High energy accelerator Research Organization (KEK)
Innovation Center for Applied Superconducting Accelerator

Innovation Center for Applied Superconducting Accelerators
応用超伝導加速器イノベーションセンター

EUV-FEL Light Source Study Group for Industrialization



THE UNIVERSITY OF TOKYO
S. Ishihara (Leader)

Utsunomiya Univ.
T. Higashiguchi

Univ. of Hyogo
T. Watanabe

Waseda Univ.
M. Washio

Osaka Univ.
T. Kozawa

KYUSHU UNIVERSITY
H. Mizoguchi

THE UNIVERSITY OF TOKYO
I. Matsuda

Industries

KIOXIA
Proterial, Ltd.
MITSUBISHI HEAVY INDUSTRIES MECHATRONICS SYSTEMS, LTD.
TAIYO NIPPON SANSO
MITSUBISHI ELECTRIC
NTT AT
TOSHIBA
GIGAPHOTON
HITACHI
TOYAMA
Canon
CANON ELECTRON TUBES & DEVICES CO., LTD.
NIHON KOSHUHA CO., LTD.
リソテックジャパン株式会社 Litho Tech Japan

Industrialization of High Power EUV light source based on ERL@KEK and FEL@QST

QST R. Hajima

KEK H. Kawata et al.

AIST T. Itani

Special Thanks

Workshop secretary; <u>Hitomi Kusama, Hisako Ohata, & Atsuko Irie</u>

10 Years ago, it seemed to be hard to believe the future lithography based on EUV-FEL Light source for general audiences.

However, few years ago, several people really started to dream the future lithography based on the EUV-FEL, and now, real construction of EUV-FEL has been started by xLight Inc. in US and the R&D of key elements of the FEL has been started by KEK in Japan.

We hope to realize **the New Era of EUV exposure system with EUV-FEL light source in a near future.**

Therefore, we need a strong support from the communities of semiconductor people.

Let’s us continue the further discussion at the Networking event!

10th WORKSHOP

EUV-FEL

January 28, 2026

13:10-16:55 JST **Hybrid**

Akihabara UDX Gallery NEXT / Conference NEXT1
Akihabara UDX 4F, 4-14-1, Sotokanda, Chiyodaku, Tokyo

EUV-FEL Light Source Study Group for Industrialization, iCASA/ KEK

KEK

Photo-session

please turn on your camera and make a smile.

Have a good day!

Good evening!

And good night!